PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Das et al. Serial No.: 10/045,542 Filed: October 26, 2001 Confirmation No.: 3570 Group Art Unit: 1762 Examiner: Michael. E. Barr

For: METHOD OF FABRICATING AN OXIDE LAYER ON A SILICON CARBIDE LAYER UTILIZING AN ANNEAL IN A HYDROGEN

ENVIRONMENT

Date: January 20, 2004

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT UNDER 37

C.F.R. § 1.97(b)

Sir:

Attached is a list of documents on form PTO-1449 together with copies of each identified document. This Information Disclosure Statement is submitted in accordance with 37 C.F.R. § 1.97(c), before final Office Action or Allowance, whichever is earlier.

Please find attached a check in the amount of \$180.00 for the fee specified in 37 C.F.R. § 1.17(p). The Commissioner is authorized to charge any additional fee or credit any refund to Deposit Account No. 50-0220.

Respectfully submitted,

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FORM PTO-1449 U.S. Department of Commerce Patent and Trademark Office					Attorney Docket Number 5308-157IP2			Serial No. 10/045,542
LIST	OF DO	OCUMENTS CITE	D BY APPLI	CANT				
TPA	U	Jse several sheets if	necessary)					
02					Applicants: Das et al.			
JAN 2 2 2004 6					Filing Date: October 26, 2001			Group: 1762
CE TRADEMARY			U. S	S. PATENT DO	CUMENTS			
Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date if Appropriate
	1	5,479,316	12/26/95	Smrtic et al.		361	322_	
	2	5,739,564	04/14/98	Kosa et al.		257	298	
	3	6,228,720	05/08/01	Kitabatake et	al.	438	268	
	4	6,239,463	05/29/01	Williams et a		257	328	_
	5	6,316,791	11/13/01	Schorner et al	•	257	77	
	6	6,593,620	07/15/03	Hshieh et al.		257	335	
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		Document Number	Date	Со	untry	Class	Subclass	Translation Yes No
	7	WO 98/02924	01/22/98	PCT				
	8	WO 00/13236	03/09/00	PCT				
		OTHER DOO	CUMENTS (I	ncluding Author	, Title, Date, Pe	rtinent Pages	, Etc.)	
	9 Dimitrijev et al., "Nitridation of Silicon-Dioxide Films Grown on 6H Silicon Carbide", <i>IEEE I Device Letters</i> , Vol. 18, No. 5, May 05, 1997, pp. 175-177.							EEE Electronic
	10	De Mao et al., "Thermal Oxidation of SiC in N2O", J. Electrochem. Soc., Vol. 141, 1994, pp. L150-L152						
	11	Ryu et al., Articl						